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Park(10) **Pub. No.: US 2006/0139554 A1**(43) **Pub. Date: Jun. 29, 2006**(54) **LIQUID CRYSTAL DISPLAY PANEL AND
FABRICATING METHOD THEREOF****Publication Classification**(76) Inventor: **Jong Woo Park**, Buk-gu (KR)(51) **Int. Cl.****G02F 1/1345** (2006.01)(52) **U.S. Cl.** **349/152**

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(57)

ABSTRACT(21) Appl. No.: **11/260,287**(22) Filed: **Oct. 28, 2005**(30) **Foreign Application Priority Data**

Dec. 23, 2004 (KR) P2004-111516

This invention relates to a liquid crystal display panel adapted to prevent corrosion of a pad electrode and reduce a liquid crystal margin area, and a fabricating method thereof. A liquid crystal display panel includes first and second substrates bonded with a sealant; a signal line on the first substrate; a pad formed on a different plane than the signal line; and a contact part overlapping the sealant and connecting the signal line to the pad.

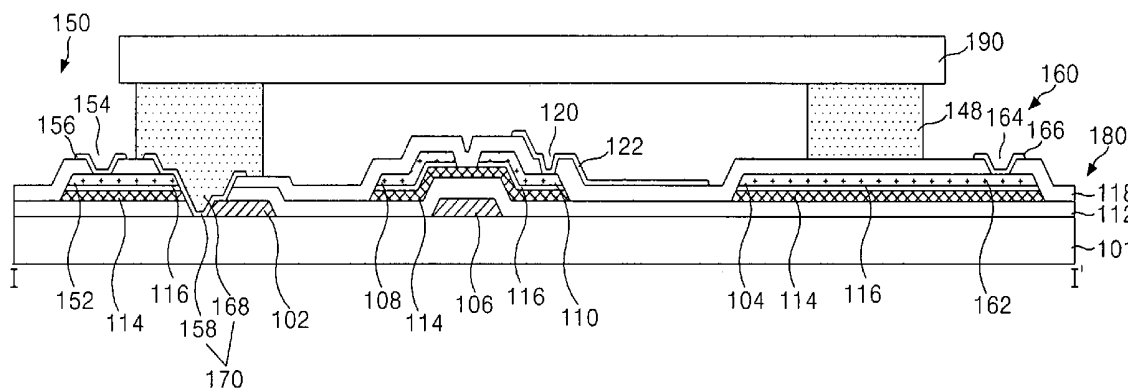


FIG. 1
RELATED ART

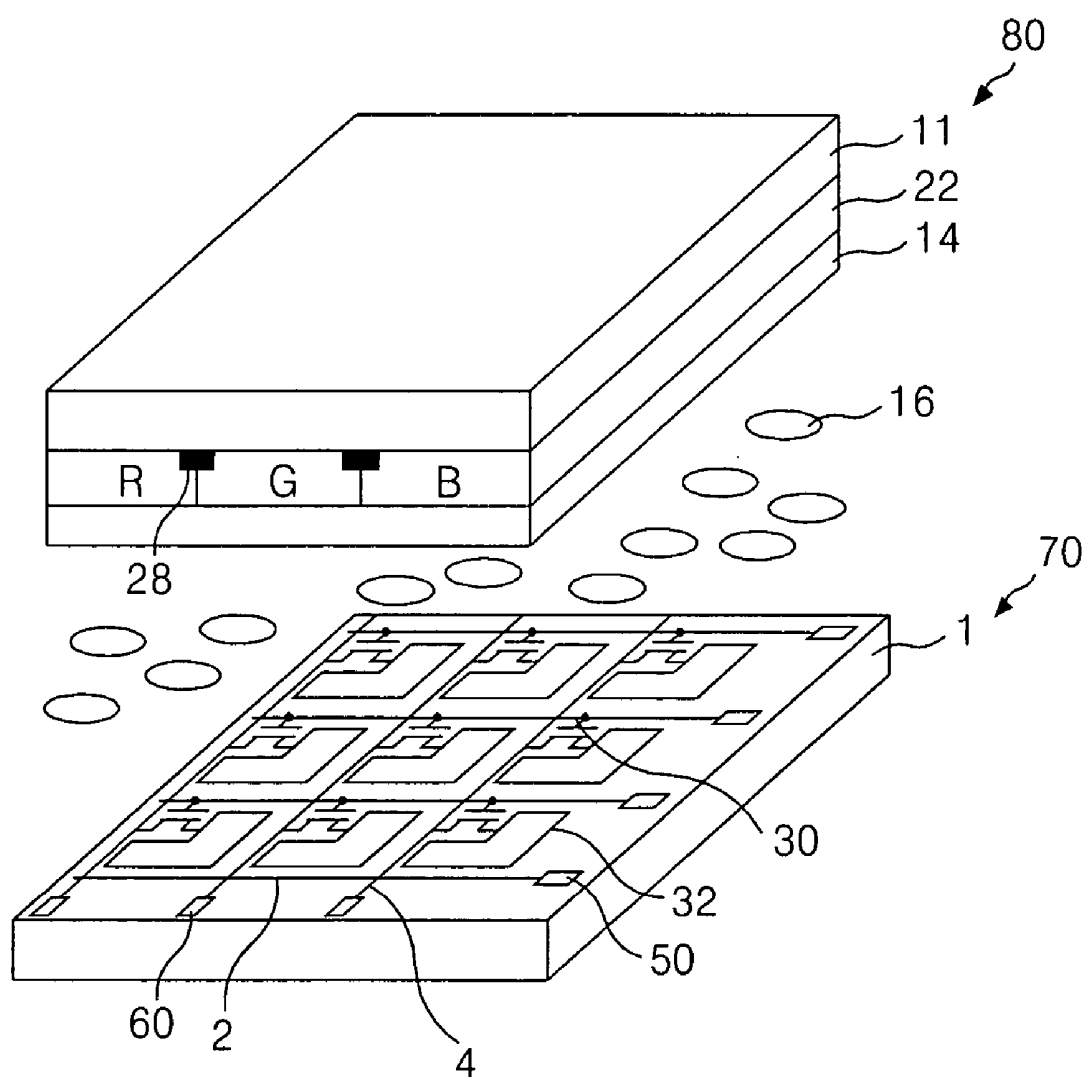


FIG. 2A

RELATED ART

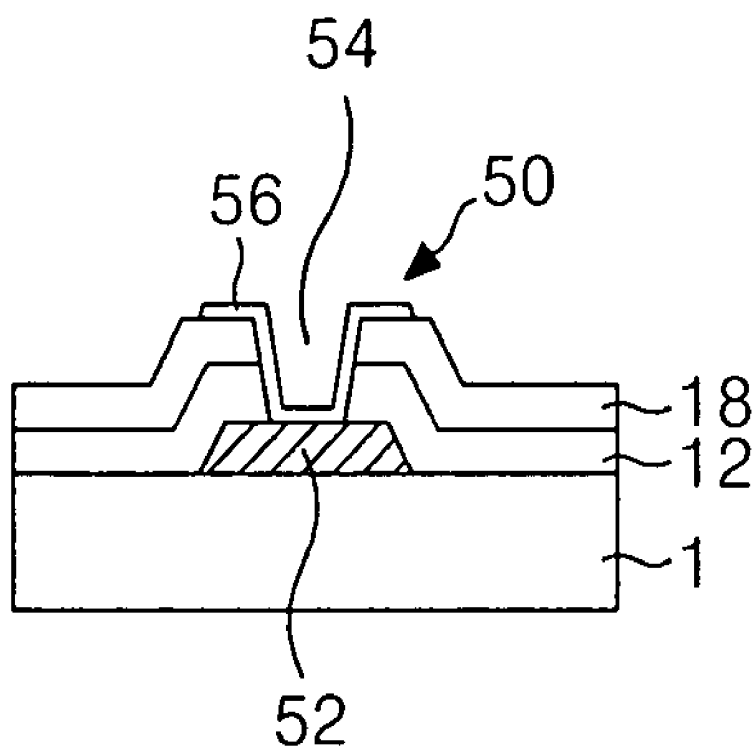


FIG. 2B

RELATED ART

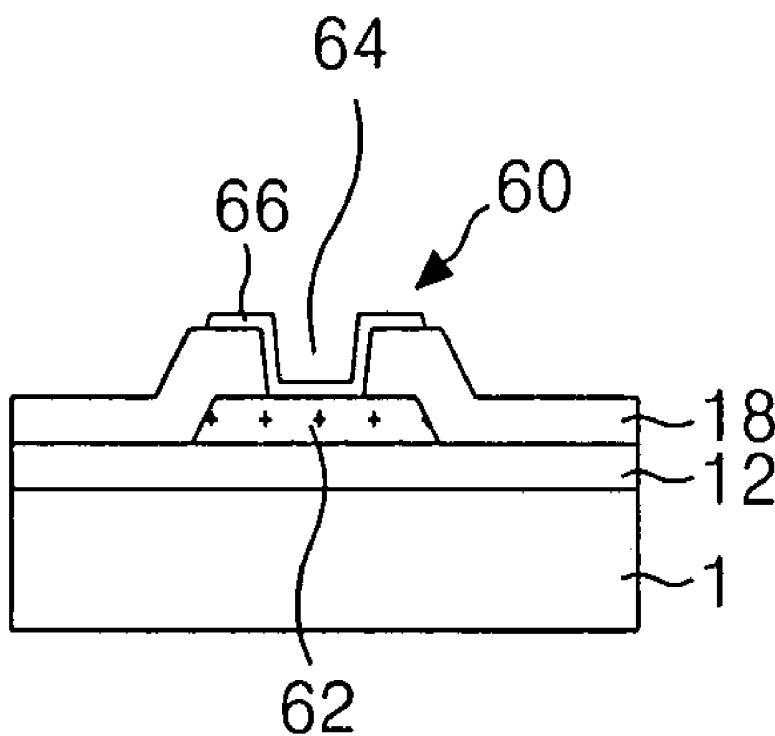


FIG. 3

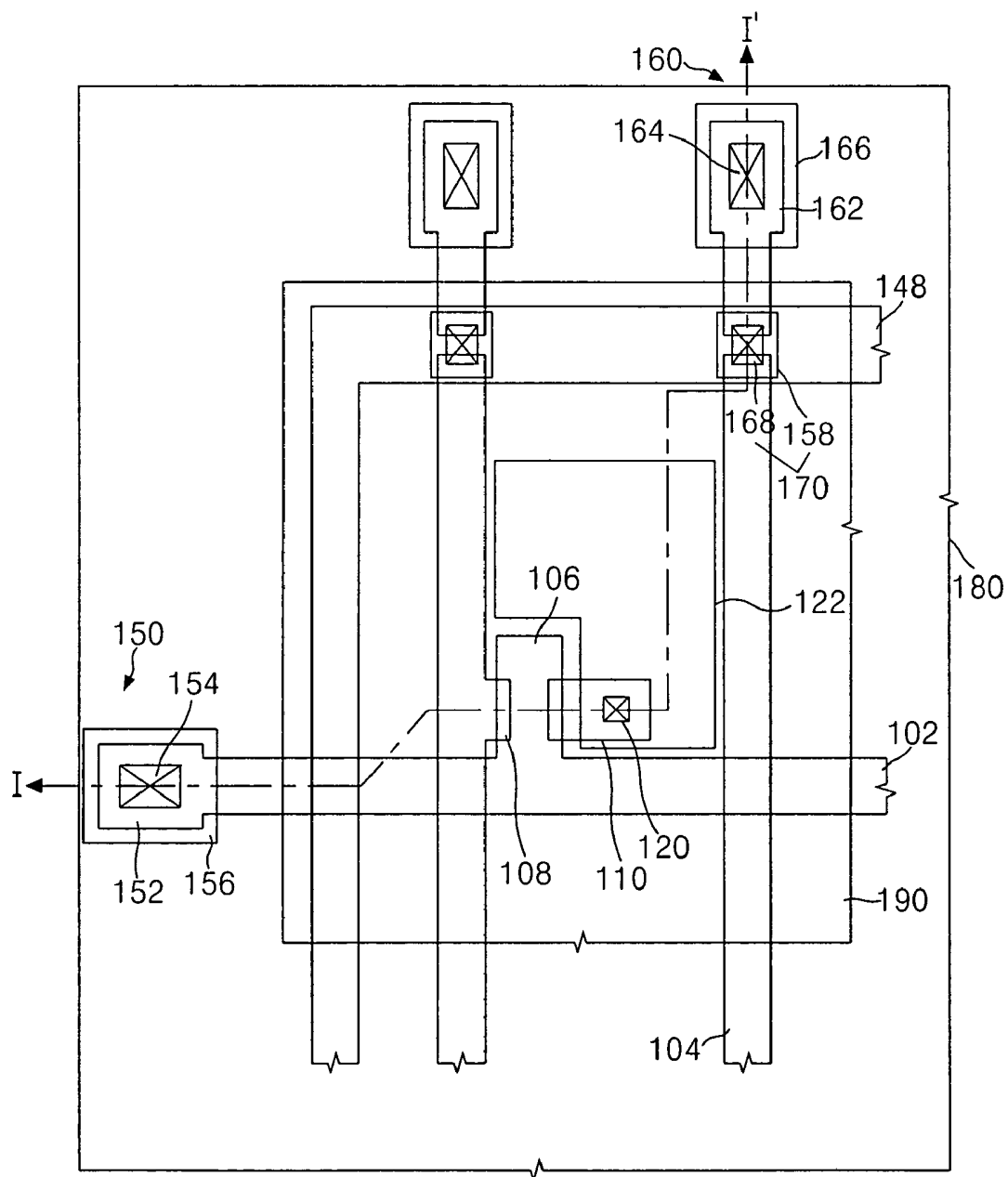


FIG. 5B

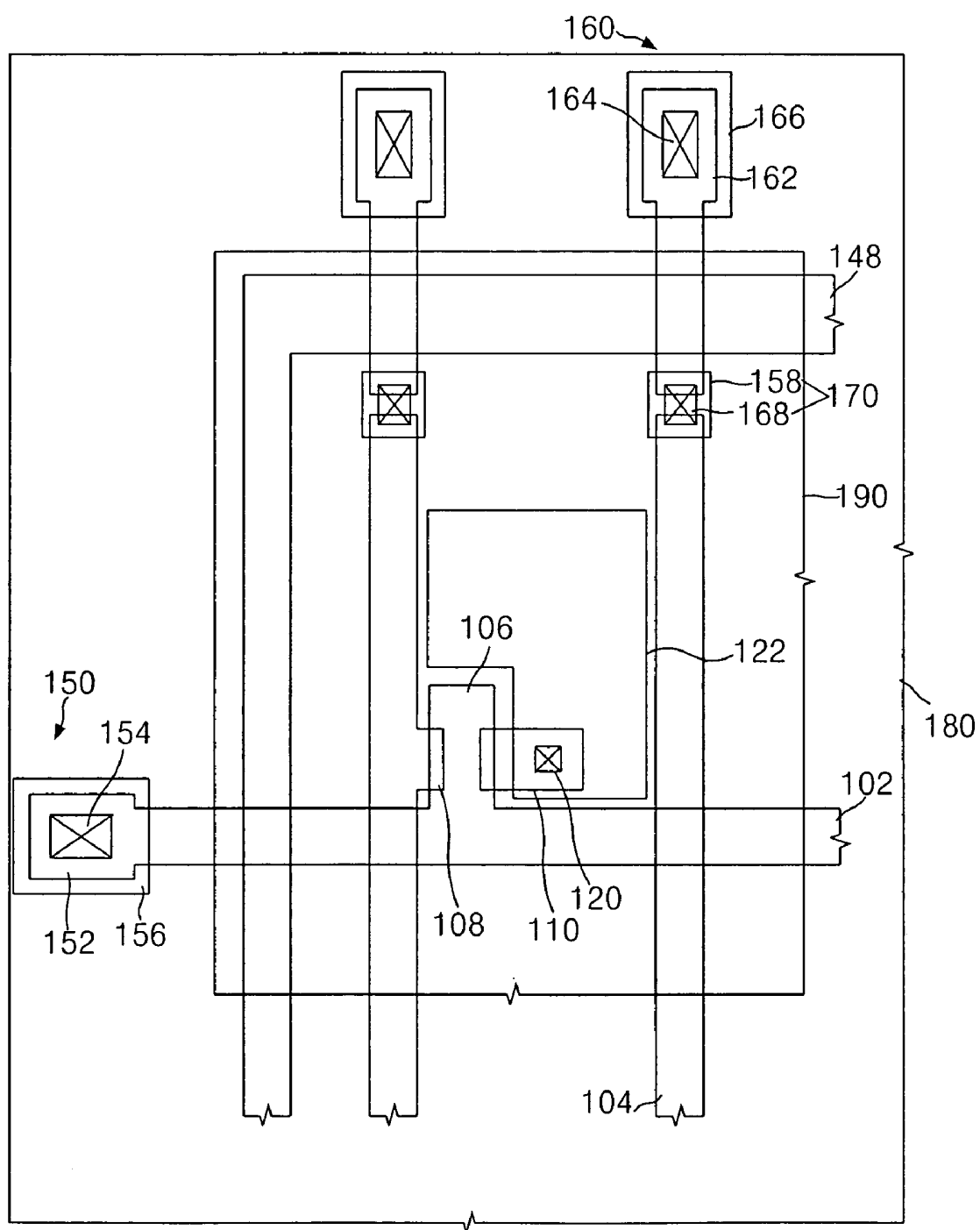


FIG. 6A



FIG. 6B

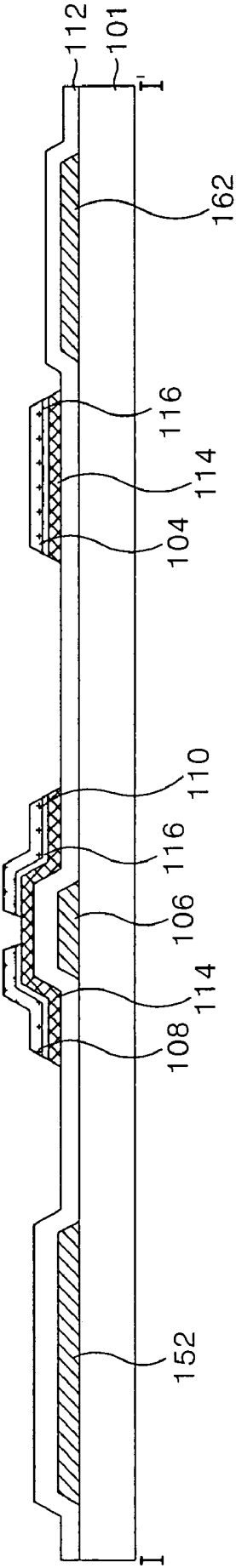


FIG. 6D

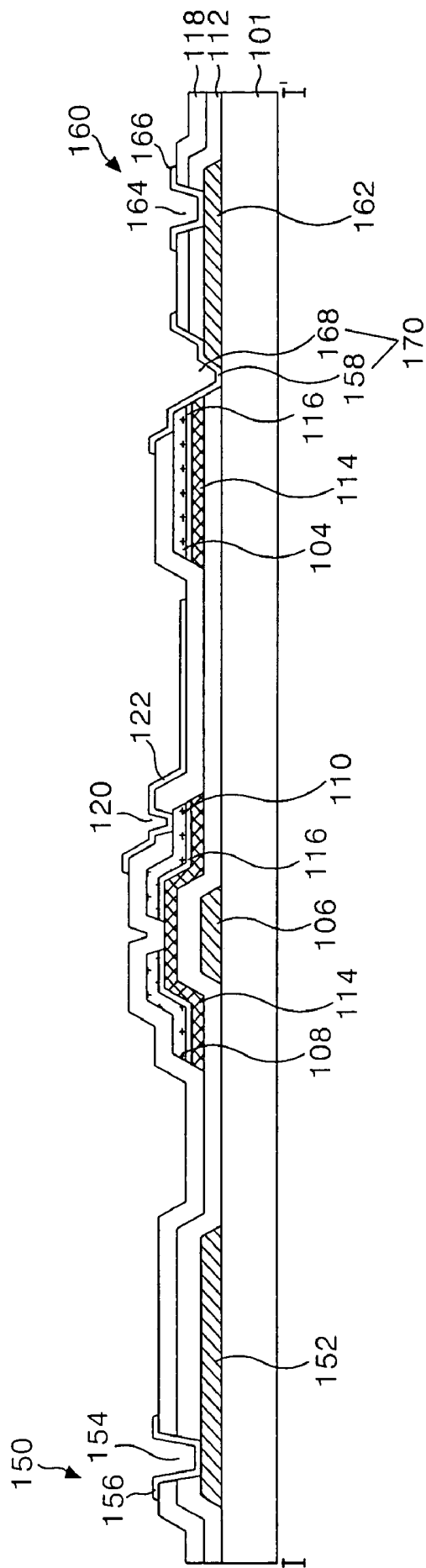


FIG. 8

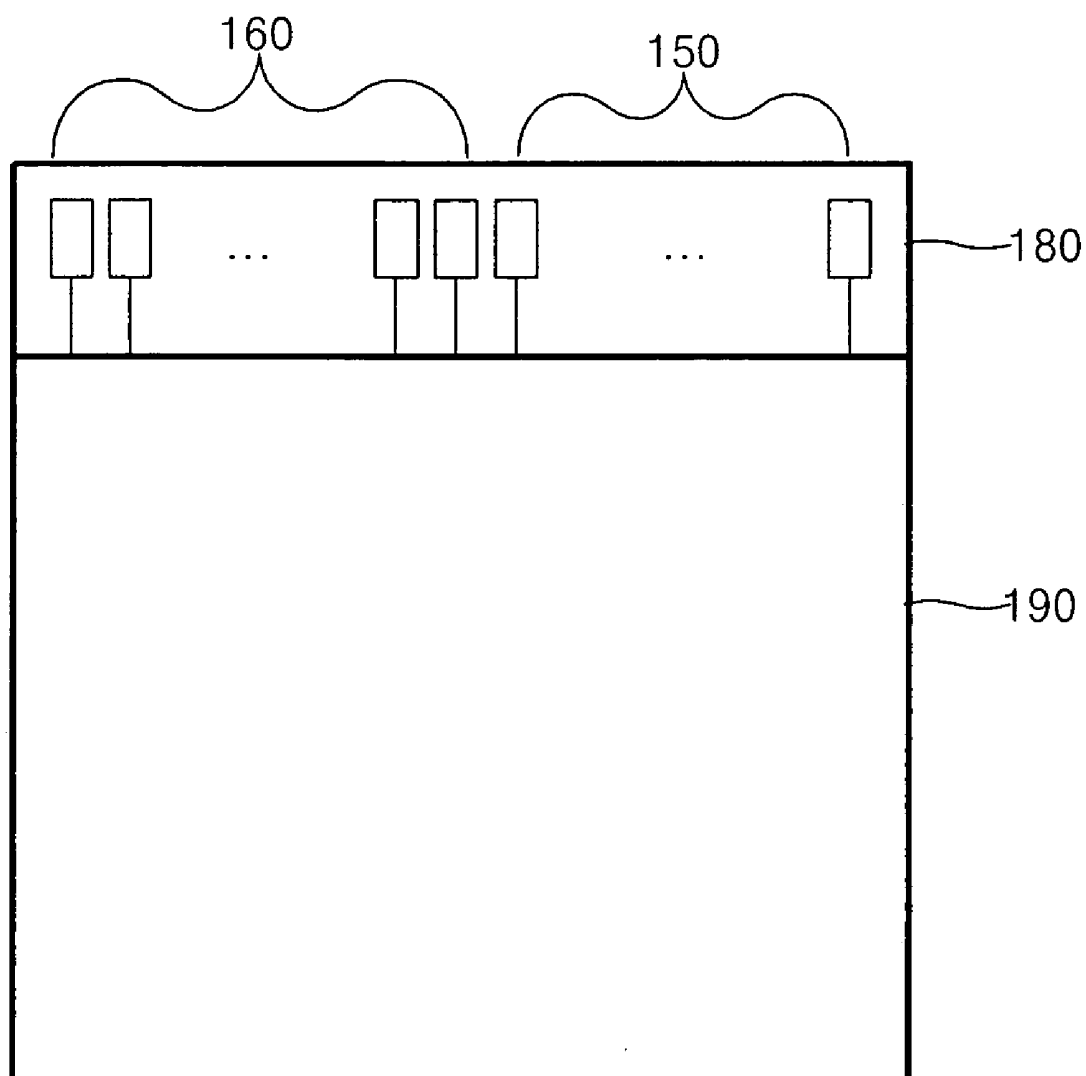
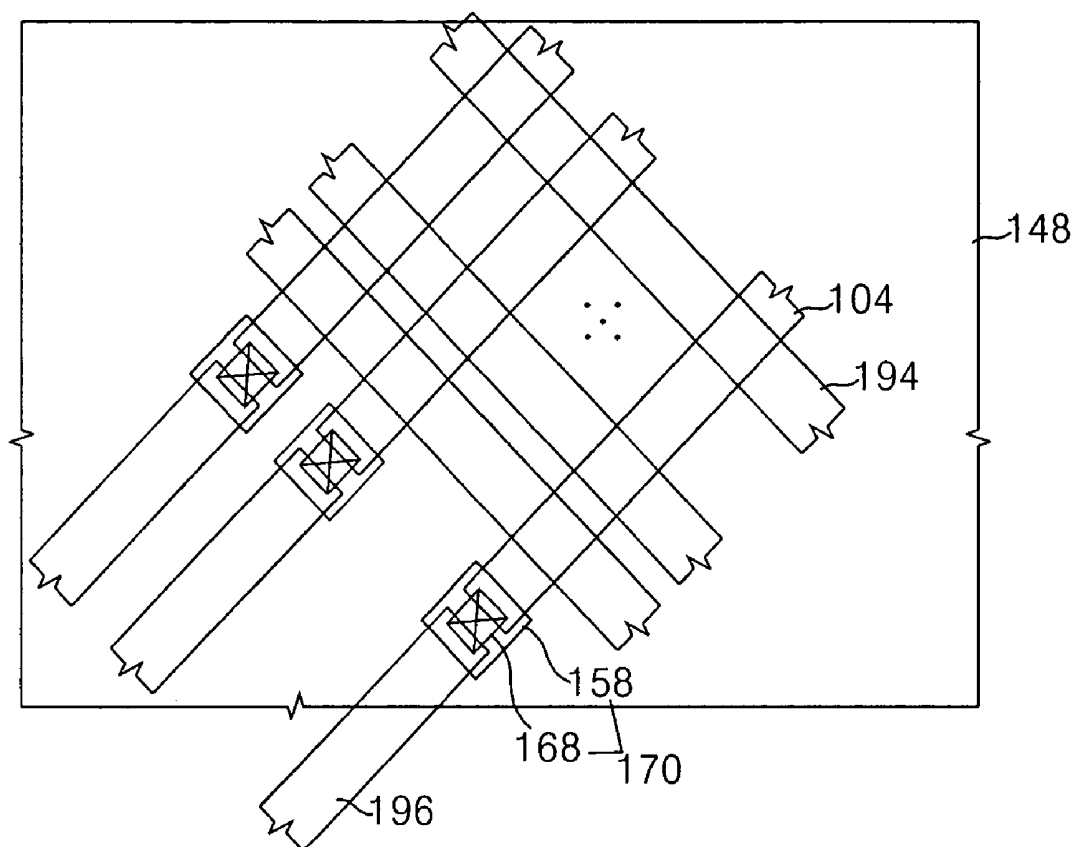


FIG. 9



LIQUID CRYSTAL DISPLAY PANEL AND FABRICATING METHOD THEREOF

[0001] This application claims the benefit of Korean Patent Application No. P2004-111516 filed on Dec. 23, 2004, which is hereby incorporated by reference for all purposes as if fully set forth herein.

BACKGROUND OF THE INVENTION

[0002] 1. Field of the Invention

[0003] The present invention relates to a liquid crystal display panel and a fabricating method thereof, and more particularly to a liquid crystal display panel that is adapted to prevent corrosion of a pad electrode and reduce a liquid crystal margin area, and a fabricating method thereof.

[0004] 2. Description of the Related Art

[0005] Generally, a liquid crystal display device (LCD) has liquid crystal cells which are arranged in a matrix shape in a liquid crystal display panel. The liquid crystal display device controls its light transmittance using a video signal to display a picture.

[0006] The liquid crystal display device, as shown in **FIGS. 1 and 2**, includes a thin film transistor substrate **70** and a color filter substrate **80** which oppose each other with a liquid crystal layer **16** therebetween.

[0007] In the color filter substrate **80**, a color filter array having a black matrix **28** for preventing light leakage, a color filter **22** for realizing color, a common electrode **14** that forms a vertical electric field with a pixel electrode **32**, and an upper alignment film (not shown) for aligning liquid crystal are formed on an upper substrate **11**.

[0008] In the thin film transistor substrate **70**, a thin film transistor array including a gate line **2** and a data line **4** formed to cross each other, a thin film transistor formed at a crossing of the gate line **2** and the data line **4**, a pixel electrode **32** connected to the thin film transistor **30**, and a lower alignment film (not shown) for aligning liquid crystal are formed on a lower substrate **1**.

[0009] The gate line **2** is connected to a gate driver (not shown) through a gate pad **50**. The gate pad **50**, as shown in **FIG. 2A**, includes a gate pad lower electrode **52** extended from the gate line **2**, and a gate pad upper electrode **56** connected to the gate pad lower electrode **52** through a gate contact hole **54** which penetrates a gate insulating film **12** and a passivation film **18**.

[0010] The data line **4** is connected to a data driver (not shown) through a data pad **60**. The data pad **60**, as shown in **FIG. 2B**, includes a data pad lower electrode **62** extended from the data line **4**, and a data pad upper electrode **66** connected to the data pad lower electrode **62** through a data contact hole **64** which penetrates the passivation film **18** above a gate insulating film **12**.

[0011] There is a problem in the related art in that the etching of a transparent conductive material to form the data pad upper electrode **66** and the gate pad upper electrode **56**, as well as the gate contact hole **54** and the data contact hole **64**, causes corrosion of the data pad lower electrode **62**. In this case, there is a problem as a data signal cannot be

supplied to the data line **4** because the data pad lower electrode **62** is not in contact with the data pad upper electrode **66**.

SUMMARY OF THE INVENTION

[0012] Accordingly, the present invention is directed to a liquid crystal display panel and a fabricating method thereof that substantially obviates one or more of the problems due to limitations and disadvantages of the related art.

[0013] An advantage of the present invention is to provide a liquid crystal display panel adapted to prevent corrosion of a pad electrode and reduce a liquid crystal margin area.

[0014] Another advantage of the present invention is to provide a fabricating method of the liquid crystal display panel.

[0015] Additional features and advantages of the invention will be set forth in the description which follows, and in part will be apparent from the description, or may be learned from practice of the invention. The objectives and other advantages of the invention will be realized and attained by the structure and method particularly pointed out in the written description and claims hereof as well as the appended drawings.

[0016] To achieve these and other advantages and in accordance with the purpose of the present invention, as embodied and broadly described, a liquid crystal display panel includes first and second substrates bonded with a sealant; a signal line on the first substrate; a pad formed on a different plane than the signal line; and a contact part overlapping the sealant and connecting the signal line to the pad.

[0017] In another aspect of the present invention, a method of fabricating a liquid crystal display panel includes forming a signal line on a first substrate; forming a pad on a different plane than the signal line; forming a contact part connecting the signal line to the pad; and forming a sealant bonding the first substrate and a second substrate in an area, the contact part overlapping the sealant in the area.

BRIEF DESCRIPTION OF THE DRAWINGS

[0018] The accompanying drawings, which are included to provide a further understanding of the invention and are incorporated in and constitute a part of this specification, illustrate embodiments of the invention and together with the description serve to explain the principles of the invention.

[0019] In the drawings:

[0020] **FIG. 1** is a perspective view representing a liquid crystal display panel of the related art;

[0021] **FIGS. 2A and 2B** are sectional diagrams representing a gate pad and a data pad shown in **FIG. 1**;

[0022] **FIG. 3** is a plan view representing a liquid crystal display panel according to an embodiment of the present invention;

[0023] **FIG. 4** is a sectional diagram representing a liquid crystal display panel taken along the line I-I' of **FIG. 3**;

[0024] **FIGS. 5A and 5B** are plan views for explaining a defect phenomenon associated with the location of a contact part shown in **FIG. 4**;

[0025] **FIGS. 6A to 6D** are sectional diagrams for explaining a fabricating method of a thin film transistor substrate shown in **FIG. 4**;

[0026] **FIG. 7** is a sectional diagram representing a liquid crystal display panel according to another embodiment of the present invention;

[0027] **FIG. 8** is a plan view representing a liquid crystal display panel according to a yet another embodiment of the present invention; and

[0028] **FIG. 9** is a plan view representing a link connected to a gate pad and a data pad shown in **FIG. 8**.

DETAILED DESCRIPTION OF THE ILLUSTRATED EMBODIMENTS

[0029] Reference will now be made in detail to embodiments of the present invention, examples of which are illustrated in the accompanying drawings.

[0030] The liquid crystal display panel shown in **FIGS. 3 and 4** includes a thin film transistor substrate **180** and a color filter substrate **190** opposing each other with a liquid crystal layer therebetween. The liquid crystal display panel also includes a lower substrate **101**.

[0031] The color filter substrate **190** includes a gate line **102** and a data line **104** crossing each other, a thin film transistor formed at a crossing thereof, and a pixel electrode **122** connected to the thin film transistor and formed in part in first contact hole **120**.

[0032] The thin film transistor selectively supplies a data signal from the data line **104** to the pixel electrode **122** in response to a gate signal from the gate line **102**. The thin film transistor includes a gate electrode **106** connected to the gate line **102**, a source electrode **108** included in the data line **104**, a drain electrode **110** connected to the pixel electrode **122**, an active layer **114** overlapping the gate electrode **106**, wherein a gate insulating film **112** is formed therebetween and forms a channel between the source electrode **108** and the drain electrode **110**, and an ohmic contact layer **116** enabling the active layer **114** to be in ohmic-contact with the source electrode **108** and the drain electrode **110**.

[0033] The pixel electrode **122** is connected to the drain electrode **110** in a pixel area provided by a crossing of the data line **104** and the gate line **102**. The pixel electrode **122** generates an electric field due to a potential difference with a common electrode (not shown) using a data signal supplied through the thin film transistor. The electric field causes the liquid crystal to rotate, and light transmittance varies according to the extent of rotation of the liquid crystal.

[0034] The gate line **102** is connected to a gate driver (not shown) through a gate pad **150**. The gate pad **150** includes a gate pad lower electrode **152** extending from the gate line **102** and a gate pad upper electrode **156** connected to the gate pad lower electrode **152** through a second contact hole **154** which penetrates a gate insulating film **112** and a passivation film **118**. The gate pad lower electrode **152** is formed of the same gate metal material as the gate line **102** or a double

layered structure of the gate metal material. For example, the gate metal material includes Al group, Mo group, Cr group, Cu group, Al alloy, Mo alloy, Cr alloy and/or Cu alloy.

[0035] The data line **104** is connected to a data driver (not shown) through the data pad **160**. The data pad **160** includes a data pad lower electrode **162** connected through a contact part **170** to the data line **104**, and a data pad upper electrode **166** connected to the data pad lower electrode **162** through a third contact hole **164** which penetrates the gate insulating film **112** and the passivation film **118**. The data pad lower electrode **162** is formed of the same gate metal material as the gate line **102** or a double layered structure of the gate metal material, for example, Al group, Mo group, Cr group, Cu group, Al alloy, Mo alloy, Cr alloy and/or Cu alloy.

[0036] The contact part **170** is formed in an area that overlaps a sealant **148**. The contact part **170** includes a fourth contact hole **168** which exposes the data line **104** and the data pad lower electrode **162**, and a contact electrode **158** for connecting the data line **104** and the data pad lower electrode **162** which are exposed through the fourth contact hole **168**. The fourth contact hole **168** penetrates the gate insulating film **112** and the passivation film **118** to expose the end of each of the data line **104** and the data pad lower electrode **162**. Specifically, the fourth contact hole **168** exposes the end of each of the data line **104** and a data link (not shown). The contact electrode **158** is formed of a transparent conductive material such as indium tin oxide (ITO), indium zinc oxide (IZO), tin oxide (TO), or indium tin zinc oxide (ITZO).

[0037] The contact part shown in **FIGS. 3 and 4** may prevent damage of the contact electrode **158**, the data line **104**, and the data pad lower electrode **162** caused by outside moisture or impurities compared to the contact part **170** formed outside the sealant **148**, as shown in **FIG. 5A**. Accordingly, the liquid crystal display panel shown in **FIGS. 3 and 4** has an improved reliability compared to the liquid crystal display panel shown in **FIG. 5A**.

[0038] Further, the contact part **170** shown in **FIGS. 3 and 4** may reduce a liquid crystal margin area compared to the case when the contact part **170** is formed in an active area which is limited by the sealant **148**, as shown in **FIG. 5B**. Herein, the liquid crystal margin area is located in the active area into which the liquid crystal is formed, but is an area where no picture is realized. The liquid crystal display panel shown in **FIG. 4**, in which the liquid crystal margin area is reduced, may have a reduced substrate size compared to the liquid crystal display panel shown in **FIG. 5B**. Thus, the liquid crystal display panel can be made in a small size.

[0039] In this way, the liquid crystal display panel according to the present invention enables the signal line to be connected to the pad electrode through the contact part. Furthermore, the liquid crystal display panel according to the present invention forms the contact part to overlap the sealant. Accordingly, it is possible to prevent corrosion of the electrode in the contact part and reduce the liquid crystal margin area.

[0040] **FIGS. 6A to 6D** are sectional diagrams representing a fabricating method of a transfective thin film transistor substrate of a liquid crystal display panel shown in **FIG. 4**.

[0041] Referring to **FIG. 6A**, a first conductive pattern group having the gate line (not shown), the gate electrode

106, the gate pad lower electrode **152** and the data pad lower electrode **162** is formed on a lower substrate **101**.

[0042] A gate metal layer is formed on the lower substrate **101** by a deposition method such as sputtering. The gate metal layer is patterned by a photolithography process and an etching process, thereby forming the first conductive pattern group having the gate line, the gate electrode **106**, the gate pad lower electrode **152** and the data pad lower electrode **162**. The gate metal layer is made of metal such as Al group metals and has a single or double layered metal structure.

[0043] Referring to **FIG. 6B**, a gate insulating film **112** is formed on the lower substrate **101** where a first conductive pattern group is formed. A semiconductor pattern having an active layer **114** and an ohmic contact layer **116** and a second conductive pattern group including the data line **104**, the source electrode **108** and the drain electrode **110** are formed thereon.

[0044] The gate insulating film **112**, an amorphous silicon layer, an amorphous silicon layer doped with impurities, and a source/drain metal layer are sequentially formed on the lower substrate **101** where the first conductive pattern group is formed by a deposition method such as plasma enhanced chemical vapor deposition (PECVD) or sputtering. The gate insulating film **112** is formed of an inorganic insulating material such as silicon oxide (SiO_x) or silicon nitride (SiN_x), and the source/drain metal layer is formed of Al group, Mo group, Cr group, Cu group, Al alloy, Mo alloy, Cr alloy and Cu alloy, or a double layered structure of thereof.

[0045] Then, there is formed a photo-resist pattern where a channel part on the source/drain metal layer has a lower height than in another part of the source/drain metal layer. The source/drain metal layer is patterned by a wet etching process using the photo-resist pattern, thereby forming the second conductive pattern group including the drain electrode **110** that is integrated with the source electrode **108**.

[0046] Then, the amorphous silicon layer doped with the impurities and the amorphous silicon layer are simultaneously patterned by a dry etching process using the same photo-resist pattern, thereby forming the ohmic contact layer **116** and the active layer **114**.

[0047] Then, after removing the photo-resist pattern which has a relatively low height in the channel part by an ashing process, the source/drain pattern and the ohmic contact layer **116** of the channel part are etched by the dry etching process. Accordingly, the active layer **114** of the channel part is exposed and the source electrode **108** is separated from the drain electrode **110**.

[0048] Subsequently, the photo-resist pattern remaining on the second conductive pattern group is removed by a stripping process.

[0049] Referring to **FIG. 6C**, the passivation film **118** having first to fourth contact holes **120**, **154**, **164** and **168** is formed on the substrate **101** where the second conductive pattern group is formed.

[0050] The passivation film **118** is formed on the gate insulating film **112** where the second conductive pattern group is formed. The passivation film **118** is formed of an inorganic insulating material similar to the gate insulating film **112** or an organic insulating material such as acrylic

resin, BCB and so on. The passivation film **118** is patterned by a photolithography process and an etching process to form the passivation film having the first to fourth contact holes **120**, **154**, **164** and **168**. The first contact hole **120** penetrates the passivation film **118** to expose the drain electrode **110** of the thin film transistor, the second contact hole **154** penetrates the gate insulating film **112** and the passivation film **118** to expose the gate pad lower electrode **152**, the third contact hole **164** penetrates the gate insulating film **112** and the passivation film **118** to expose the data pad lower electrode **162**, and the fourth contact hole penetrates the gate insulating film **112** and the passivation film **118** to expose the end of the data line **104** and the end of the data pad lower electrode **162**.

[0051] Referring to **FIG. 6D**, a third conductive pattern group having the pixel electrode **122**, the gate pad upper electrode **156**, the data pad upper electrode **166** and the contact electrode **158** is formed on the passivation film **118**. Contact part **170** is also formed.

[0052] A transparent conductive layer is formed on the passivation film **118** by a deposition method such as sputtering. The transparent conductive layer is patterned by a photolithography process and an etching process, thereby forming the third conductive pattern group having the pixel electrode **122**, the gate pad upper electrode **156**, the data pad upper electrode **166** and the contact electrode **158**. The transparent conductive layer is formed of ITO, TO, IZO or ITZO. Gate pad **150** and data pad **160** are formed.

[0053] **FIG. 7** is a plan view representing a liquid crystal display panel according to another embodiment of the present invention.

[0054] The liquid crystal display panel shown in **FIG. 7** has the same components as the liquid crystal display panel shown in **FIGS. 3 and 4** except that the gate pad lower electrode **152** and the gate line **102** are formed of a different metal. Accordingly, a detailed description of the same components will be omitted.

[0055] The lower electrodes **152**, **162** of the gate pad **150** and the data pad **160** are formed of the source/drain metal layer. In this case, the contact part **170** for connecting the gate pad **150** and the gate line **102** is formed to overlap the sealant **148**. The contact part **170** includes a contact hole **168** that exposes the end of the gate line **102** and the end of the gate pad lower electrode **152**, and a contact electrode **158** that connects the gate line **102** to the gate pad lower electrode **152** through the contact hole **168**.

[0056] **FIG. 8** is a plan view representing a liquid crystal display panel according to yet another embodiment of the present invention, and **FIG. 9** is a plan view representing a link part of **FIG. 8**. Herein, the gate pad and the data pad shown in **FIG. 8** are formed in one structure of the gate pad and the data pad shown in **FIGS. 4 and 7**. The gate pad and the data pad of the liquid crystal display panel according to this embodiment of the present invention will be explained by taking the gate pad **150** and the data pad **160** shown in **FIG. 4** as an example.

[0057] The liquid crystal display panel shown in **FIG. 8** has the gate pad **150** and the gate pad **160** located in parallel in the same area to enable reduction of substrate size. In this case, a gate link **194** located between the gate pad **150** and the gate line and a gate link **196** located between the data pad

160 and the data line are formed in a crossing structure as shown in FIG. 9. The contact part 170 for connecting the data link 196 and the data line 104 which are formed on a difference plane from the crossing part is formed to overlap the sealant 148.

[0058] In this way, the liquid crystal display panel according to this embodiment of the present invention has the contact part 170 and the crossing part between the gate link 196 and the gate link 194 formed to overlap the sealant. Thus, the liquid crystal margin area is reduced compared to the liquid crystal display panel where the crossing part and the contact part are formed inside the active area. Accordingly, the size of the substrate may be reduced by as much as the reduced liquid crystal margin area. Thus, the liquid crystal display panel according to the this embodiment of the present invention can be made small in size.

[0059] The above-described embodiments of the present invention may be applicable to a transmissive type, a reflective type, a transfective type, a TN (Twisted Nematic) mode and a IPS (In Plane Switching) mode liquid crystal display device, and its application is not limited to the above-described mode.

[0060] As described above, the liquid crystal display panel and the fabricating method thereof according to the present invention has the contact part formed to overlap the sealant. The contact part connects the signal line and the pad electrode, which are formed of different metals on different planes. Accordingly, the liquid crystal display panel and the fabricating method thereof according to the present invention may prevent damage of the electrode, which is formed inside the contact part, caused by moisture and impurities. Further, the contact part of the liquid crystal display panel which is formed in the fabricating method thereof overlaps the sealant. Thus, in the liquid crystal display panel according to the present invention, the liquid crystal margin area is reduced compared to a liquid crystal display panel where the contact part is formed inside the active area. Accordingly, the size of the substrate can be reduced by as much as the reduced liquid crystal margin area. Thus the liquid crystal display panel according to the present invention may be applied in small size.

[0061] It will be apparent to those skilled in the art that various modifications and variation can be made in the present invention without departing from the spirit or scope of the invention. Thus, it is intended that the present invention cover the modifications and variations of this invention provided they come within the scope of the appended claims and their equivalents.

What is claimed is:

1. A liquid crystal display panel, comprising:

first and second substrates bonded with a sealant;

a signal line on the first substrate;

a pad formed on a different plane than the signal line; and

a contact part overlapping the sealant and connecting the signal line to the pad.

2. The liquid crystal display panel according to claim 1, wherein the signal line is at least one of a data line and a gate line.

3. The liquid crystal display panel according to claim 2, wherein the pad includes:

a data pad lower electrode formed on a different plane from a data line;

a contact hole penetrating an insulating film to expose the data pad lower electrode; and

a data pad upper electrode connected to the data pad lower electrode through the contact hole.

4. The liquid crystal display panel according to claim 3, wherein the data pad lower electrode is formed of a same metal on a same plane as a gate line.

5. The liquid crystal display panel according to claim 3, further comprising:

a gate pad lower electrode extending from a gate line;

a second contact hole penetrating the insulating film to expose the gate pad lower electrode; and

a gate pad upper electrode connected to the gate pad lower electrode through the second contact hole.

6. The liquid crystal display panel according to claim 3, wherein the contact part includes:

a contact hole exposing the end of each of the data line and the data pad lower electrode; and

a contact electrode connecting the data line and data pad lower electrode that are exposed through the contact hole.

7. The liquid crystal display panel according to claim 5, wherein the gate pad and the data pad are located in parallel on a same area of the first substrate.

8. The liquid crystal display panel according to claim 1, wherein the first substrate is a thin film transistor substrate and the second substrate is a color filter substrate.

9. The liquid crystal display panel according to claim 8, wherein the color filter substrate includes a gate line and a data line crossing each other and a thin film transistor formed at a crossing thereof.

10. The liquid crystal display panel according to claim 9, wherein the color filter substrate further includes a pixel electrode connected to the thin film transistor and formed in part in a contact hole.

11. The liquid crystal display panel according to claim 9, wherein the thin film transistor includes a gate insulating film formed between a gate electrode and an active layer.

12. The liquid crystal display panel according to claim 9, wherein a gate insulating film forms a channel between a source electrode and a drain electrode.

13. A method of fabricating a liquid crystal display panel, comprising:

forming a signal line on a first substrate;

forming a pad on a different plane than the signal line;

forming a contact part connecting the signal line to the pad; and

forming a sealant bonding the first substrate and a second substrate in an area, the contact part overlapping the sealant in the area.

14. The method according to claim 13, wherein forming the signal line includes:

forming at least one of a gate line and a data line on the first substrate.

15. The method according to claim 13, wherein forming the pad includes:

forming a data pad lower electrode on a different plane than a data line;

forming a contact hole penetrating an insulating film to expose the data pad lower electrode; and

forming a data pad upper electrode connected to the data pad lower electrode through the contact hole.

16. The method according to claim 15, wherein the data pad lower electrode is formed of a same metal on a same plane as a gate line.

17. The method according to claim 15, further comprising:

forming a gate pad lower electrode extended from a gate line;

forming a second contact hole penetrating the insulating film to expose the gate pad lower electrode; and

forming a gate pad upper electrode connected to the gate pad lower electrode through the second contact hole.

18. The method according to claim 15, wherein forming the contact part includes:

forming a contact hole exposing an end of each of the data line and the data pad lower electrode; and

forming a contact electrode connecting the data line and data pad lower electrode that are exposed through the contact hole.

* * * * *

专利名称(译)	液晶显示面板及其制造方法		
公开(公告)号	US20060139554A1	公开(公告)日	2006-06-29
申请号	US11/260287	申请日	2005-10-28
[标]申请(专利权)人(译)	朴钟W		
申请(专利权)人(译)	朴钟W		
当前申请(专利权)人(译)	LG DISPLAY CO. , LTD.		
[标]发明人	PARK JONG WOO		
发明人	PARK, JONG WOO		
IPC分类号	G02F1/1345		
CPC分类号	G02F1/1341 G02F1/1345 G02F1/13458 G02F1/136227		
优先权	1020040111516 2004-12-23 KR		
其他公开文献	US7796227		
外部链接	Espacenet USPTO		

摘要(译)

液晶显示面板及其制造方法本发明涉及一种适于防止焊盘电极腐蚀并减小液晶边缘区域的液晶显示板及其制造方法。液晶显示面板包括用密封剂粘合的第一和第二基板;第一基板上的信号线;形成在与信号线不同的平面上的焊盘;接触部分与密封剂重叠并将信号线连接到焊盘。

